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## (54) THERMOPLASTIC RESIN COMPOSITION

## (57)Abstract:

PROBLEM TO BE SOLVED: To obtain a thermoplastic resin composition comprising an aromatic polycarbonate resin excellent in fatigue strength and mechanical strengths at high temperatures and high humidities and a styrene-based resin by making the most of characteristics such as impact resistance and molding processability essentially possessed by the aromatic polycarbonate resin and the styrene-based resin.

SOLUTION: This thermoplastic resin composition comprises (A) 1-99 wt.% of an aromatic polycarbonate resin having  $\leq 2\%$  residual catalyst activity index and obtained by reacting a dihydric phenol with a carbonate precursor according to a melting method and (B) 99-1 wt.% of a styrene-based resin. The carbonate precursor is diphenyl carbonate and the content of hydroxy group terminals of the aromatic polycarbonate is 0-40 mol% based on the total terminals. Furthermore, the styrene-based resin is polystyrene, a high-impact polystyrene, an acrylonitrile-styrene copolymer, a methyl methacrylate-butadiene-styrene copolymer or an acrylonitrile-butadiene-styrene copolymer.

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